

L Number	Hits	Search Text	DB	Time stamp
1	1532545	memory or floating adj gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:37
2	62887	silicide or salicide or polycide or policide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:32
3	2619892	source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:56
4	3375698	throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:34
5	166	source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4 (silicide or salicide or polycide or policide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:41
6	57	(memory or floating adj gate) and (source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4 (silicide or salicide or polycide or policide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:35
8	47	((memory or floating adj gate) and (source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4 (silicide or salicide or polycide or policide))) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:37
9	1532545	memory or floating adj gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:37
10	47	(memory or floating adj gate) and (source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4 (silicide or salicide or polycide or policide)) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:43
11	7158	(over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:41
12	7	source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4 ((over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 14:42
13	5	(memory or floating adj gate) and (source near4 (throughhole or through adj hole or viahole or via adj hole or via or interconnect\$4 or inter adj connect\$4) near4 ((over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide))) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:05
14	41951	common near2 source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:02

15	6	((over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide)) near4 (common near2 source)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:05
16	29	((over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide)) same (common near2 source)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:05
17	6	((over or upper or above or top or cap or capping) near2 (silicide or salicide or polycide or policide)) same (common near2 source)) and (memory or floating adj gate) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:22
20	2	("5280446" "5656527").PN.	USPAT	2004/09/16 15:10
21	61421	self adj align\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:57
22	158394	inplant or implant or implanting or implanting	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 15:57
23	26866	ild or (interlevel or intermediate) near2 (dielectric or oxide or insulat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:01
24	687259	planar\$4 or cmp or polish\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:01
25	6015	(silicide or salicide or polycide or policide) near2 gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:01
26	2387	(self adj align\$4) near4 (inplant or implant or implanting or implanting)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:02
27	1	((self adj align\$4) near4 (inplant or implant or implanting or implanting)) and (ild or (interlevel or intermediate) near2 (dielectric or oxide or insulat\$4)) same (planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:21
28	21	(ild or (interlevel or intermediate) near2 (dielectric or oxide or insulat\$4)) same (planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:25
29	13	((ild or (interlevel or intermediate) near2 (dielectric or oxide or insulat\$4)) same (planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:28
30	23	(planar\$4 or cmp or polish\$4) near4 (expos\$4 or open\$4 or top) near4 gate same ((silicide or salicide or polycide or policide) near2 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:33

31	12	((planar\$4 or cmp or polish\$4) near4 (expos\$4 or open\$4 or top) near4 gate same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:33
32	12	((planar\$4 or cmp or polish\$4) near4 (expos\$4 or open\$4 or top) near4 gate same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")) not (((ild or (interlevel or intermediate) near2 (dielectric or oxide or insulat\$4)) same (planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:28
33	362	(planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:34
34	228	((planar\$4 or cmp or polish\$4) same ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:34
35	59	(planar\$4 or cmp or polish\$4) near8 ((silicide or salicide or polycide or policide) near2 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 16:34
36	39	((planar\$4 or cmp or polish\$4) near8 ((silicide or salicide or polycide or policide) near2 gate)) and (@ad < "20010111")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 17:00
37	2	5869396.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 17:01
38	2	5869396.pn. and (planar\$4 or cmp or polish\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 17:01
39	3043	((438/626) or (438/647) or (438/645) or (438/649) or (438/257)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/16 17:23
-	1	6720579.pn.	USPAT	2004/09/16 13:12
-	1	6376876.pn.	USPAT	2004/09/16 15:56